第 89 回研究会（平成 8 年 11 月 20、21、22 日、京都）
－国際シンポジウム－
「次世代の原子レベルキャラクタリゼーションを探る」

ALC’96
Nov.20-22, 1996
The Palace Side Hotel, Kyoto

SIMS & SNMS1
1. “Fundamental Aspects of Laser Post Ionization SNMS for Film Characterization: Experimental Studies and Computer Simulations”, G. Bets, W. Husinsky (Technical Univ. of Wien)
2. “Laser Post-Ionizations SNMS”, S. Hayashi (Nippon Steel Corp.)
3. “Atom Counting by Laser Post Ionization Technique”, S. Ichimura (ETL)

SIMS & SNMS2
4. “Cs Ion Source: Its Development and Application for SIMS”, H. Storms (General Electric Corp.)
5. “Applications of SIMS for Earth Sciences”, H. Yurimoto (Tokyo Institute of Technology)
6. “Application of Secondary Ion Mass Spectrometry (SIMS) to Biology and Medicine”, K. Takaya, M. Okabe, T. Yoshida (Toyama Medical and Pharmaceutical Univ.)

Fine Electron Source
8. “Ultra Small Energy Spread Emitter at Low Temperature”, C. Oshima (Waseda Univ.)

SEM and Surface Plasmon
11. “SEM Observation of Surface Step Dynamics - Sublimation and Phase Transition on Si(111)”, Y. Homma (NTT)
12. “Study of Surface Electronic Excitation with HREELS and ELS-LEED”, M. Rocca (Genova Univ.)


15. “Atomic Structure and Growth Mode of the Cu/Si(111) Quasi-$5 \times 5$ Surface Studied by Scanning LEED Microscopy and Scanning Tunneling Microscopy”, T. Ichinokawa (Waseda Univ.)

16. “Surface Electric Conductivity and Electro-Migration by SEM”, S.Ino (Univ. of Tokyo)

17. “New Methods (SFG and STM) of Atomic Characterization of Surfaces at High Pressures and During Reactions”, G. A. Somorjai (Univ. of California)


20. “X-Ray Photoelectron Diffraction as a Tool for Characterization of the Structures of Solid Surfaces”, Y. Nihei (Univ. of Tokyo)